



Docket No. 500.39826CX1/E5828-04EU

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant : Seiichiro KANNO *et al.*  
Serial No. : 10/679,342  
Filed : 7 October 2003  
For : SEMICONDUCTOR MANUFACTURING APPARATUS  
AND METHOD OF PROCESSING SEMICONDUCTOR  
WAFER USING PLASMA AND WAFER VOLTAGE PROBE  
Art Unit : Unassigned (Parent - 1763)  
Examiner : Unassigned (Parent - Ram N. Kackar)  
Conf. No. : Unassigned (Parent - 4591)

**SUPPLEMENTAL PRELIMINARY AMENDMENT**

Commissioner for Patents  
POB 1450  
Alexandria, Virginia 22313-1450

10 December 2003

Sir:

Supplemental to and after entry of the Preliminary Amendment filed 7 October 2003, and prior to examination on the merits in the above-identified application, the following amendments and remarks are respectfully submitted.

In accordance with the revised format of the manner of making amendments under 37 CFR §1.121 as set forth in the Final Rule effective 30 July 2003, each section of amendment herein begins on a new page, and changes are shown by strike-through (or double brackets where appropriate) and underlining to indicate deletions and additions, respectively. A complete listing of all claims ever presented in the application is given with the current status of each claim, and only the text of all pending and withdrawn claims is presented in full, with those not being amended herein being presented in clean version.